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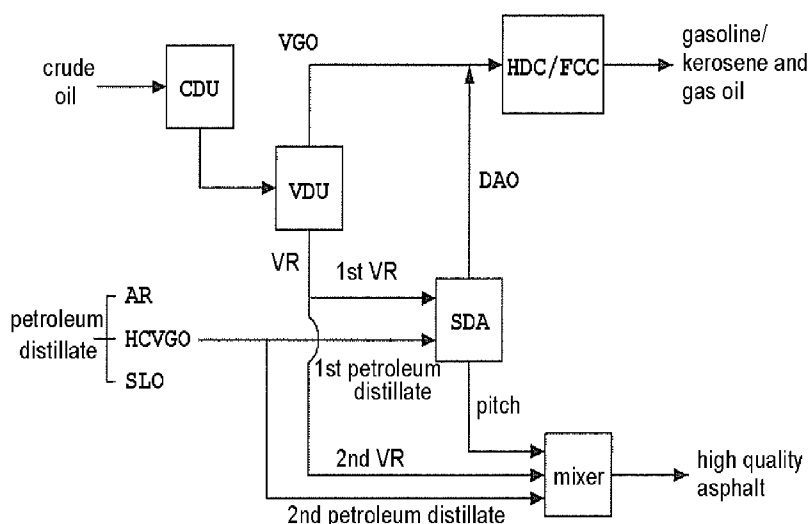
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(54) Title: HIGH QUALITY ASPHALT CONTAINING PITCH AND METHOD OF PREPARING THE SAME



(57) Abstract: Disclosed herein are high quality asphalt containing pitch that is generated as a by-product in a solvent deasphalting process and a method of preparing the same. Specifically, this invention provides high quality asphalt containing pitch, the pitch being obtained by subjecting a mixture comprising a first vacuum residue and a first petroleum distillate, which is lighter than the vacuum residue and has high amounts of aromatic and resin, to solvent deasphalting, and a method of preparing such high quality asphalt. According to the method of this invention, the operation conditions of the solvent deasphalting process are appropriately controlled, such that aromatic and resin components contained in the atmospheric residue and vacuum residue can be distributed to the pitch, and as well, a saturate can be removed. Thus, compared to conventional methods of preparing asphalt using only the vacuum residue, the wax content and ductility after a thin film oven test can be more improved.

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